

## Main Unit Spec

Model Type	i-Line (365 nm) Stepper
Wafer Size	300 mm, 200 mm
Resolution	≤ 500 nm
Numerical Aperture (NA)	0.28 ~ 0.37
Reticle Size	6 in. (0.25 in. thick)
Reduction Ratio	2:1
Field Size	52 mm (max) x 56 mm (max) (diam. 70.7 mm max)
Overlay Accuracy	≤ 50 nm ( m  + 3σ)
Footprint (W x D x H)	2,300 mm × 3,340 mm × 2,700 mm
Options	Low Oxygen Exposure (LOX) Extended AGA (EAGA) Wide-Band OAS (WB-OAS) Pellicle Particle Checker Chemical Filtering Resist Outgassing Unit PC Remote Console Online Functions (GEM2, GEM0304)